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### (54) MANUFACTURE OF SUBSTRATE FOR LIQUID CRYSTAL DISPLAY DEVICE

(57)Abstract:

**PROBLEM TO BE SOLVED:** To prevent occurrence of flaws on the rear surface of an active matrix substrate in the middle of a manufacture process.

**SOLUTION:** A first rear-surface oxide film 3, a rear-surface polysilicon film 4 and a second rear-surface oxide film 5 are formed on the rear surface of a transparent insulating substrate 1. A thin film transistor 10 is formed via a base oxide film 6 on the surface of the substrate, and coated with an interlayer film 16. A contact hole is formed and a wiring electrode 21 and a pad electrode 22 are formed, and a transparent electrode 23 is formed. The substrate surface is covered with a photoresist film 31, and the second rear-surface oxide film 5, the rear-surface polysilicon film 4 and the first rear-surface oxide film 3 are etched by a wet method. Then, the photoresist film 31 is removed.

